

Amendments to the Specification:

Please replace the paragraph bridging pages 6 and 7, with the following amended paragraph:

A column direction of hologram patterns of the hologram member of the optical pickup device of this invention is preferably aligned with the longer axis direction of the far field pattern of the real laser light source. The far field pattern is ~~ellipsoidal~~ elliptic and indicates a cross sectional intensity distribution of light fluxes at a position spaced apart by about 10 to 20 cm from a semiconductor laser emission point. A light spread angle is larger in the longer axis direction than in the shorter axis direction so that a light output having a more uniform intensity can be obtained in the longer axis direction than in the shorter axis direction. With the column direction of the hologram patterns aligned with the longer axis direction of the far field pattern, light can be applied at a similar intensity both to the hologram pattern at the distal end of the hologram member and to the other hologram patterns. It is therefore possible to form imaginary laser light sources having a similar intensity to that of the real laser light source, and to lower a difference between intensities of light applied to the hologram patterns. Since a plurality of light spots having a small intensity difference can be applied to an optical disk, it is possible to suppress a variation in data signals read from the optical disk and photoelectrically converted. The quality of a data signal can therefore be prevented from being degraded. Since the hologram member is disposed, in a state capable of receiving light of a uniform intensity, at a position relatively remote from the real laser light source, the angle θ described with reference to Fig. 9 can be made small so that astigmatism and coma of a light spot can be reduced.

Please replace the paragraph beginning at page 13, line 5, with the following amended paragraph:

The real laser light source 11 is disposed so that the longer axis direction of its far field pattern becomes coincident with the column direction of the non-diffraction and diffraction hologram patterns 14, 15a, 15b, and 15c of the hologram module 13. The far field pattern of the real laser light source 11 is ~~ellipsoidal~~ elliptic. The light intensity of the far field pattern maintains a predetermined value or higher in a longer span along the longer axis direction of the ellipsoid. Therefore, with the longer axis direction set as described above, the light intensity of the imaginary laser light sources 12a, 12b, and 12c can be made uniform along the longer axis direction. The nondiffraction and diffraction hologram patterns 14, 15a, 15b, and 15c may be an amplitude hologram pattern with bright and dark interference fringes or a phase hologram pattern with binary or blazed grooves formed on glass or the like.